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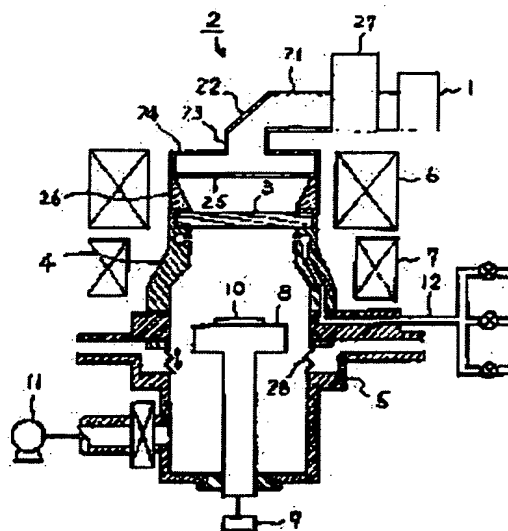
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(54) MICRO WAVE PLASMA PROCESSING DEVICE AND PLASMA PROCESSING METHOD

(57)Abstract:

PURPOSE: To evenly process a sample at a high speed by using the micro wave so as to appropriately set the high density area of the plasma to be generated in a plasma processing chamber.

CONSTITUTION: A resonator 24 for resonantly oscillating the micro wave at the specified mode is fitted to a micro wave transmitting means 2 for supplying the micro wave, which is generated by a micro wave generator 1, to a plasma generating space 4. A waveguide 26 for gradually changing the diameter of the cross section of an opening formed over from the resonator 24 to the plasma generating space 4 is fitted.



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